

Title (en)
HIGH-RESOLUTION OVERLAY ALIGNMENT METHODS AND SYSTEMS FOR IMPRINT LITHOGRAPHY

Title (de)
HOCH AUFLÖSENDE AUSRICHTUNGSVERFAHREN UND ENTSPRECHENDE SYSTEME FÜR DIE PRÄGE-LITHOGRAPHIE

Title (fr)
PROCEDES D'ALIGNEMENT DE SUPERPOSITIONS A HAUTE RESOLUTION ET SYSTEMES DE LITHOGRAPHIE DE SURIMPRESSION

Publication
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Application
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Priority

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Abstract (en)
[origin: WO0208835A2] A method of determining and correcting alignment during imprint lithography process is described. During an imprint lithographic process the template may be aligned with the substrate by the use of alignment marks disposed on both the template and substrate. The alignment may be determined and corrected for before the layer is processed.

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